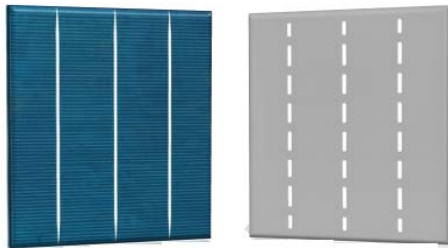


Data sheet Cella 3BB

	Specification					Physical location:
	<h2 style="text-align: center;">Technical Data sheet</h2>					
DMS loc.:	Rev.:	Doc.:	Rev. date:	Doc. owner:		
8100.03E	03	FO	28-05-2013	QA		
Cell Type: H-pattern / segmented Back-side Configuration 01						

Description



Cell Layout_GEN_03

Dimensions	Qualification	Permitted Deviation
Feature		
Outer dimensions	156mm x 156mm	± 0.5 mm
Cell thickness nominal as ordered	on wafer level	± 30 µm
Bow	Cell placed on flat surface sunny side up. Distance between centre of cell and flat surface	<= 2,5mm.



Front surface		
Width of busbar	1,4 mm	± 0,1 mm
Number of busbar	3	
Distance between centre busbar and outer busbar	52,0	± 0,2 mm
Material of busbar	Silver	

Back surface		
Width of busbar	2,5 mm	± 0,5 mm
Number of segments	3	
Length of segment interruption	2,5 mm	± 0,5 mm
Number of busbar	3	
Distance between centre busbar and outer busbar	52,0	± 0,2 mm
Material of busbar	Silver	
Material of the surrounding parts of the back surface of the cell	Aluminum	

Electrical properties		
Power	Power classes according to P_{max} at standard test conditions (STC, AM 1.5, 1000 W/m ² , 25°C) Accuracy of measurement ± 1.5% relative to ISE certified reference cell	Divided in classes, see below
Reverse bias criteria	Reverse dark measurement $V_{bias} = -12 V$ allowed current $V_{bias} = -6 V$ allowed current measurement accuracy ± 2%	$I_{bias} < 2.0 A$, $I_{bias} < 0.4 A$.
Shunt resistivity	(Dark I-V measurement) at 0V	$R_{sh} > 15 Ohm$

Typical data at STC (non encapsulated cells)*

Cellclass	Pmpp(W)	Efficiency(%)	Voc(mV)	Isc(A)
S156PS375	3.75	15.40	602	8.18
S156PS380	3.80	15.60	605	8.22
S156PS385	3.85	15.80	607	8.25
S156PS390	3.90	16.00	609	8.28
S156PS395	3.95	16.20	612	8.33
S156PS400	4.00	16.40	614	8.38
S156PS405	4.05	16.60	616	8.41
S156PS410	4.10	16.80	618	8.45
S156PS415	4.15	17.00	620	8.49
S156PS420	4.20	17.20	622	8.53
S156PS425	4.25	17.40	625	8.56
S156PS430	4.30	17.60	627	8.60